## MA5. Boron-containing Coatings:

Superhard single-phase Ti<sub>1-x</sub>Al<sub>x</sub>B<sub>y</sub> films with good oxidation resistance grown without external heating using hybrid HiPIMS/DCMS technique

<u>Bartosz Wicher</u><sup>a</sup>, Vladyslav Rogoz<sup>a</sup>, Oleksandr Pshyk<sup>a,b</sup>, Szilard Kolozsvari<sup>c</sup>, Peter Polcik<sup>c</sup>, Ivan Petrov<sup>a,d</sup>, Lars Hultman<sup>a,e</sup>, Grzegorz Greczynski<sup>a</sup>

<sup>a</sup>Thin Film Physics Division, Department of Physics (IFM), Linkoping University, Linkoping SE-58183, Sweden,

<sup>b</sup>Laboratory for Surface Science and Coating Technology, Empa, Swiss Federal Laboratories for Materials Science and Technology, Ueberlandstrasse 129, 8600 Dübendorf, Switzerland, <sup>c</sup>Plansee Composite Materials GmbH, Siebenbürgerstr. 23, Lechbruck am See, D-86983 Germany, <sup>d</sup>Materials Research Laboratory, University of Illinois, Urbana, IL 61801, United States, <sup>e</sup>Center for Plasma and Thin Film Technology, Ming Chi University of Technology, New Taipei City 24301, Taiwan

A hybrid High-Power Impulse Magnetron Sputtering (HiPIMS) and Direct Current Magnetron Sputtering (DCMS) approach with  $TiB_2$  and  $AIB_2$  targets is used to grow  $Ti_{1-x}AI_xB_y$  thin films with  $0.40 \le x \le 0.76$  and  $1.81 \le y \le 2.03$ . The hybrid sputtering method ensures precise control over the energy and momentum of ionized species. The primary aim is to optimize the Al content for enhancing the high-temperature oxidation resistance while maintaining excellent mechanical properties that stem from the diboride structure. No external substrate heating is used resulting in the substrate temperature lower than  $180^{\circ}C$ .

Oxidation tests performed at temperatures ranging from 700 to 900 °C indicate a substantial improvement in oxidation resistance with higher Al content. Films with  $x \le 0.49$  develop porous, B-depleted oxide layers containing titanium dioxide (TiO<sub>2</sub>) phase and often exhibit spallation. In contrast, Ti<sub>1-x</sub>Al<sub>x</sub>B<sub>y</sub> thin films with  $x \ge 0.58$  form compact oxide scales composed of amorphous alumina (Al<sub>2</sub>O<sub>3</sub>) and borate (Al<sub>18</sub>B<sub>4</sub>O<sub>33</sub>) phases, which effectively passivate the surface against further oxidation. The oxide scales formed on high-Al content films are much denser and exhibit markedly improved mechanical properties with increased hardness (up to 27.3 GPa, comparable to TiAlN coatings), and also a better adhesion to the underlying substrate material due to better matching of thermal expansion coefficients.

These findings offer a promising foundation for developing high-performance boride-based coatings for applications in the industries such as aerospace and power generation that require coating materials with mechanical strength and resistance to high-temperature oxidation.

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## Corresponding Author:

Bartosz Wicher E-mail: <u>bartosz.wicher@liu.se</u>